



1762
Application No. 09/863,150

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE
PATENT EXAMINING OPERATION

Applicant(s): Mark Leonard O'NEILL et al.

Serial No: 09/863,150

Group Art Unit: 1762

Filed: May 23, 2001

Examiner: Timothy Howard Meeks

Att. Docket No.: 06150 USA

Confirmation No.: 7590

For: LOW DIELECTRIC CONSTANT MATERIAL AND METHOD OF PROCESSING BY CVD

Handwritten: 4/5/03, 4/2/03, [Signature]

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AMENDMENT

Box Non-Fee Amendment
Commissioner for Patents
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Sir:

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GROUP 1700

In response to the Office Action dated January 2, 2003, please amend the above-identified application as follows:

IN THE CLAIMS:

Please amend claims 18, 27, 47, 57 and 72 as follows:

- Handwritten:* H. Chen
18. (Amended) A chemical vapor deposition method comprising:
- a. providing a substrate within a vacuum chamber;
 - b. introducing into the vacuum chamber gaseous reagents including a